ABSTRACT OF THE DISCLOSURE

Disclosed is a method and apparatus for measuring an optical characteristic of a projection optical system such as wavefront aberration, for example, very precisely. In an embodiment of the present invention, the method includes a first detecting step for causing each of plural light beams from a pattern to pass a predetermined position on a pupil plane of the optical system and subsequently imaging the light beams separately, and for detecting an imaging position of each light beam upon the pupil plane of the optical system, a second detecting step for detecting error information related to a passage position as each light beam passes through the pupil plane, and a third detecting step for detecting wavefront aberration of the optical system on the basis of the imaging position of each light beam upon the pupil plane and of the error information related to the passage position of each light beam on the pupil plane.